AMENDMENTS TO THE CLAIMS:

This listing of claims will replace all prior versions, and listings, of claims in the application:

Claims 1-7 (Canceled).

8. (New) A method of manufacturing a silicon wafer, the method comprising: polishing side faces of a silicon block used for manufacturing the silicon wafer;

slicing the silicon block.

and

- 9. (New) The method of claim 8, wherein the polished side faces of the silicon block have a surface roughness Ry of $8\mu m$ or less.
- 10. (New) A method of manufacturing a silicon inclusive wafer, the method comprising:

polishing side faces of a block comprising silicon, which is used for manufacturing the silicon inclusive wafer; and slicing the block.

KAJIMOTO et al. Appl. No. To be Assigned November 20, 2003

11. (New) The method of claim 10, wherein at least one polished side face of the block has a surface roughness Ry of $8\mu m$ or less.